

<b>Notice of References Cited</b>	Application/Control No. 10/678,003	Applicant(s)/Patent Under Reexamination PADHI ET AL.	
	Examiner Edna Wong	Art Unit 1753	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-2007/0014075	01-2007	Ritter et al.	361/306.3
*	C	US-6,174,812	01-2001	Hsiung et al.	438/687
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	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

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	U	Moiseeva et al., "Palladium-Copper Alloy Electrodeposition with a Pulsed Current", Intensifik. Tekhnol. Protsessov pri Gsazhdenil Met. I Splavov (no month, 1997), pp. 92-93, From: Ref. Zh. Metall, 1978, Abstr. No. 2G293. Abstract only.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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